

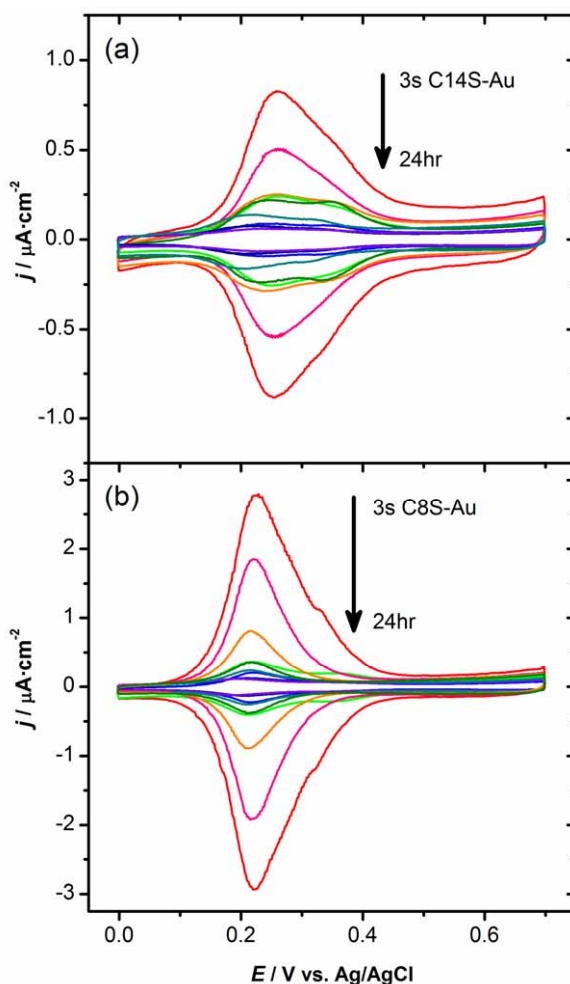
Supporting Information

# Ferrocenylalkylthiolate Labeling of Defects in Alkylthiol Self-Assembled Monolayers on Gold

*Lawrence YoonSuk Lee and R. Bruce Lennox\**

Department of Chemistry and the FQRNT Centre for Self-Assembled Chemical Structures, McGill University, 801 Sherbrooke Street West, Montreal, Quebec, H3A 2K6, Canada

\* Corresponding author. Tel.: 514-398-3638. Fax: 514-398-3797. E-mail: [bruce.lennox@mcgill.ca](mailto:bruce.lennox@mcgill.ca)



**Figure S1.** Labeling of defects in (a) C<sub>14</sub>S-Au and (b) C<sub>8</sub>S-Au SAMs that are formed using various incubation times ranging from 3s to 24 hrs. CVs are obtained in 1.0 M HClO<sub>4</sub> at a scan rate of 20 mV·s<sup>-1</sup>,

after labeled with 2 mM FcC<sub>12</sub>SH for 5s.

**Table S1. List of Kinetics Parameters obtained from the Fitting of Data in Figure 8 to Diffusion Limited Langmuir Second-Order Equation<sup>a</sup>**

C <sub>14</sub> S-Au SAM formation conditions		<i>k</i> <sup>a</sup> (s <sup>-1/2</sup> )	<i>A</i> <sup>a</sup> (%)
Concentration	Formation time		
0 <sup>b</sup>	0 <sup>b</sup>	6.09	101.2
200 μM	5 min	0.32	11.4
200 μM	2 hrs	0.57	4.33
1 mM	5 min	0.098	14.1
1 mM	2 hrs	0.013	35.1
5 mM	24 hrs	0.006	28.1

<sup>a</sup>  $\Theta(t) = A * k * \sqrt{t} / (1 + k * \sqrt{t})$  where *A* is the final coverage and *k* is the reaction rate constant. <sup>b</sup> denotes that a bare Au electrode is used.